

Title (en)  
UNDERLAYER FILM FORMING COMPOSITION FOR SELF-ASSEMBLED FILMS

Title (de)  
UNTERSCHICHTFILMBILDENDE ZUSAMMENSETZUNG FÜR SELBSTAUFBAUENDE FILME

Title (fr)  
COMPOSITION FILMOGÈNE DE SOUS-COUCHE POUR FILMS AUTO-ASSEMBLÉS

Publication  
**EP 2832807 A4 20151021 (EN)**

Application  
**EP 13769608 A 20130322**

Priority  
• JP 2012071803 A 20120327  
• JP 2013058333 W 20130322

Abstract (en)  
[origin: EP2832807A1] There is provided an underlayer film-forming composition which is used for an underlayer for a self-assembled film. An underlayer film-forming composition for self-assembled films, comprising a polysiloxane and a solvent. The polysiloxane may be a hydrolysis-condensation product of a silane containing a phenyl group-containing silane, or a hydrolysis-condensation product of a silane containing a silane of Formula (1)  $[R_2Si(R_1)_3]$  wherein  $R_1$  is an alkoxy group, an acyloxy group, or a halogen atom, and  $R_2$  is an organic group containing a benzene ring optionally having a substituent and is a group bonded to the silicon atom through a Si-C bond, in a ratio of 10 to 100% by mol relative to the total silane, or a hydrolysis-condensation product of silanes containing the silane of Formula (1), a silane of Formula (2)  $[R_4Si(R_3)_3]$ , and a silane of Formula (3)  $[Si(R_5)_4]$  in a ratio of the silane of Formula (1):the silane of Formula (2):the silane of Formula (3) of 10 to 100:0 to 90:0 to 50 in terms of % by mol relative to the total silane:

IPC 8 full level  
**B05D 3/10** (2006.01); **C09D 5/00** (2006.01); **C09D 183/04** (2006.01); **G03F 7/11** (2006.01); **G03F 7/26** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP US)  
**B05D 1/005** (2013.01 - US); **B05D 3/0254** (2013.01 - US); **C08G 77/80** (2013.01 - EP US); **C09D 5/00** (2013.01 - EP US); **C09D 5/002** (2013.01 - EP US); **C09D 183/04** (2013.01 - EP US); **G03F 7/0002** (2013.01 - EP US); **H01L 21/0332** (2013.01 - EP US)

Citation (search report)  
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• [XYI] EP 2372458 A1 20111005 - NISSAN CHEMICAL IND LTD [JP]  
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• [XP] EP 2560049 A2 20130220 - SHINETSU CHEMICAL CO [JP]  
• See references of WO 2013146600A1

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DOCDB simple family (publication)  
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